

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1.-12. (Canceled)

13. (Currently Amended) An apparatus for adjusting a spacing between a gas distribution member and a substrate support, the apparatus comprising:

- a processing chamber including a the gas distribution member;
- a substrate support disposed in the processing chamber and located generally opposite from the gas distribution member, the substrate support having a substrate support surface configured to support a the substrate on which to form a layer;
- a leveling plate coupled to the substrate support, the leveling plate including at least three measurement locations to mount a measuring device to measure distances between the leveling plate and a reference surface fixed with respect to the gas distribution member at each of the measurement locations, each of the at least three measurement locations including an aperture in the leveling plate, the aperture configured for insertion of the measuring device; and
- at least three adjustment members each extending from ~~coupled between~~ the leveling plate to and the reference surface, each of the at least three adjustment members disposed at separate adjustment locations distributed on the leveling plate and separated from the at least three measurement locations, the at least three adjustment members ~~being disposed at separate adjustment locations distributed over the leveling plate and~~ independently adjustable to change positions of the leveling plate relative to the reference surface, ~~thereby and~~ adjusting spacings between the substrate support surface and the gas distribution member at a plurality of corresponding adjustment locations on the substrate support surface to modify a tilt of the substrate support surface with respect to the gas distribution member.

14. **(Currently amended)** The apparatus of claim 13 wherein the separate measurement locations are each disposed in proximity to adjacent one of the separate adjustment locations.

15. **(Original)** The apparatus of claim 13 wherein the leveling plate includes slots at the at least three measurement locations to temporarily mount the measurement device at each of the measurement locations.

16. **(Original)** The apparatus of claim 13 wherein the adjustment member comprises adjustment screws threadingly coupled to the leveling plate and having ends bearing against the reference surface of the processing chamber; and knurled lock nuts threadingly coupled to the adjustment screws and bearing against a surface of the leveling plate.

17. **(Currently Amended)** The apparatus of claim 13 wherein the leveling plate is generally parallel to the substrate support surface, and wherein the plurality of corresponding adjustment locations on the substrate support surface are generally aligned with the plurality of separate adjustment locations distributed on the leveling plate.

18. **(Original)** The apparatus of claim 17 wherein the plurality of corresponding adjustment locations on the substrate support surface are uniformly distributed around the substrate support surface with respect to a center of the substrate support surface.

19. **(Original)** The apparatus of claim 13 wherein the reference surface is a bottom surface of the processing chamber.

20. **(Original)** The apparatus of claim 13 wherein the gas distribution member comprises a faceplate and the reference surface is generally parallel to the faceplate.

21. **(Currently Amended)** The apparatus of claim 13 wherein the substrate support comprises a diameter and wherein each of the at least three measurement locations is

separated from one of the separate ~~a corresponding~~ adjustment locations by a distance, ~~the~~
~~distance~~ of no more than 10% of ~~a~~ the diameter of the substrate support.

22. (New) An apparatus for adjusting a spacing between a gas distribution member and a substrate, the apparatus comprising:

a processing chamber including the gas distribution member;

a reference surface fixed with respect to the gas distribution member;

a substrate support disposed in the processing chamber and located generally opposite from the gas distribution member, the substrate support having a substrate support surface configured to support the substrate on which to form a layer;

a leveling plate coupled to the substrate support, the leveling plate including at least three measurement apertures and at least three adjustment apertures, the at least three measurement apertures extending through the leveling plate to mount a measuring device to measure distances between the leveling plate and the reference surface, the at least three adjustment apertures extending through the leveling plate, each measurement aperture spaced apart from each adjustment aperture; and

at least three adjustment members each extending from the at least three adjustment apertures to the reference surface, the at least three adjustment members independently adjustable to change positions of the leveling plate relative to the reference surface and adjust spacings between the substrate support surface and the gas distribution member to modify a tilt of the substrate support surface with respect to the gas distribution member.

23. (New) The apparatus of claim 22 wherein each of the at least three measurement apertures is disposed in proximity to one of the at least three adjustment apertures.

24. (New) The apparatus of claim 22 wherein the at least three measurement apertures comprise slots to temporarily mount the measurement device at each of the measurement locations.

25. (New) The apparatus of claim 22 wherein the a least three adjustment member comprises adjustment screws threadingly coupled to the leveling plate and having ends bearing against the reference surface of the processing chamber; and knurled lock nuts threadingly coupled to the adjustment screws and bearing against a surface of the leveling plate.

26. (New) The apparatus of claim 22 wherein the leveling plate is generally parallel to the substrate support surface.

27. (New) The apparatus of claim 22 wherein the reference surface is a bottom surface of the processing chamber.

28. (New) The apparatus of claim 22 wherein the gas distribution member comprises a faceplate and the reference surface is generally parallel to the faceplate.

29. (New) The apparatus of claim 22 wherein the substrate support comprises a diameter and wherein each measurement aperture is separated from one of the at least three adjustment apertures by a distance of no more than 10% of the diameter of the substrate support.